PALM INTRANET

Day: Tuesday Date: 8/10/2004

Time: 14:55:18

Inventor Information for 10/693842

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|------------------------|------------|---------------|--|
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| Search Anoth | er: Application# | Search | or P | Patent# | Search |
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| L Number | Hits | Search Text | DB | Time stamp |
|----------|---------|---|---------------------|--------------------|
| 1 | 1906041 | photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:18 |
| | | (photosensitizer or initiator) | US-PGPUB; | |
| | | | EPO; JPO; | |
| İ | | | DERWENT | |
| 2 | 382974 | (photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:19 |
| | | (photosensitizer or initiator)) and o quinone diazide | US-PGPUB; | , , , |
| | | | EPO; JPO; | |
| | | | DERWENT | |
| 3 | 376746 | ((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:20 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | , , |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester) | DERWENT | |
| 4 | 29796 | (((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:21 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | . , |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester)) and cyclohexane | DERWENT | |
| 5 | 0 | ((((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:21 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester)) and cyclohexane) and ?diaminocyclohexane | DERWENT | |
| 6 | 0 | ((((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:31 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | 1 | sulfonic ester)) and cyclohexane) and | DERWENT | |
| | | ?methylenebiscyclohexane | | |
| 8 | 26 | (((((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:22 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester)) and cyclohexane) and 522/164.ccls.) and | DERWENT | |
| | | (polyamic acid or polyimide precursor or polyamide acid) | | |
| 9 | 22 | ((((((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:23 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester)) and cyclohexane) and 522/164.ccls.) and | DERWENT | |
| | | (polyamic acid or polyimide precursor or polyamide acid)) | | |
| 11 | EECCO4 | and (film or layer) | | |
| 11 | 556604 | ((((((((photosensitive resin composition and polyimide and | USPAT; | 2004/08/10 16:23 |
| | | (photosensitizer or initiator)) and o quinone diazide) and | US-PGPUB; | |
| | | (?trihydroxybenzophenone o naphthoquinone diazide | EPO; JPO; | |
| | | sulfonic ester)) and cyclohexane) and 522/164.ccls.) and | DERWENT | |
| | | (polyamic acid or polyimide precursor or polyamide acid)) | | |
| 10 | 11 | and (film or layer)) and alicyclic) and sulfonic ester (((((((photosensitive resin composition and polyimide and | LICDAT | 2004/00//2 / 5 5 5 |
| 10 | 11 | (((((((photoserisitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and | USPAT; | 2004/08/10 16:23 |
| | | (?trihydroxybenzophenone o naphthoquinone diazide) | US-PGPUB; | |
| | | sulfonic ester)) and cyclohexane) and 522/164.ccls.) and | EPO; JPO; | |
| | | (polyamic acid or polyimide precursor or polyamide acid)) | DERWENT | |
| | | and (film or layer)) and alicyclic |] | |
| 7 | 26 | ((((photosensitive resin composition and polyimide and | LICDAT: | 2004/00/40 45 25 |
| • | 20 | (hotosensitizer or initiator)) and o quinone diazide) and | USPAT; US-PGPUB; | 2004/08/10 16:30 |
| | ļ | (?trihydroxybenzophenone o naphthoquinone diazide) | | |
| | Ì | sulfonic ester)) and cyclohexane) and 522/164.ccls. | EPO; JPO; | |
| 12 | 1730 | ((((photosensitive resin composition and polyimide and | DERWENT | 2004/09/40 46:24 |
| | 2,00 | (photosensitizer or initiator)) and o quinone diazide) and | USPAT; US-PGPUB; | 2004/08/10 16:31 |
| | | (?trihydroxybenzophenone o naphthoquinone diazide) | EPO; JPO; | |
| ŀ | | sulfonic ester)) and cyclohexane) and (polyamic acid or | DERWENT | |
| | ļ | polyimide precursor) and photoinitiator | PLKAAEIAI | |
| | | e | l | |

| 13 | 2 | ((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and | USPAT; US-PGPUB; | 2004/08/10 16:34 |
|----|-----|--|----------------------|------------------|
| | | (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and imidiz? | EPO; JPO; DERWENT | |
| 14 | 3 | (((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and | USPAT; US-PGPUB; | 2004/08/10 16:36 |
| | | (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or | EPO; JPO; DERWENT | |
| 15 | 40 | polyimide precursor) and photoinitiator) and ?cyclohexane (((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and | USPAT; US-PGPUB; | 2004/08/10 16:42 |
| | | (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or | EPO; JPO; DERWENT | |
| | | polyimide precursor) and photoinitiator) and methylene near3 cyclohexane | | |
| 16 | 174 | (522/164).CCLS. | USPAT | 2004/08/10 17:07 |